

# ACHEMA 2009: Beiträge unter Mitwirkung von Bayer Technology Services

MONDAY	LOCATION	TIME
<b>Design of hydrophobic interaction chromatography</b> C. Bohrmann, J. Strube, TU Clausthal, Clausthal-Zellerfeld/D; M. Lohrmann, S. Sommerfeld, Bayer Technology Services GmbH, Leverkusen/D	Analog, Forum	11:30
<b>Modelling approach of phenylacetonitrile alkylation process in microreactor</b> E. S. Borovinskaya, V. A. Holodnov, St. Petersburg State University of Technology/RUS; F. Schael, Ehrfeld Mikrotechnik BTS GmbH, Wendelsheim/D; W. Reschetilowski, TU Dresden/D	Conclusio 1, CMF	16:30
<b>Key aspects to manage successfully large investment projects in PR China</b> J. Liu, Bayer Technology Engineering, Shanghai/PRC	Conclusio 2, CMF	16:30
TUESDAY	LOCATION	TIME
<b>New applications and components for a modular microreaction system</b> M. Kroschel, F. Herbstritt, K. Nagy, O. Stange, Ehrfeld Mikrotechnik BTS GmbH, Wendelsheim/D	Harmonie 3, CMF	11:00
<b>Namur Expertenrunden: Materialidentifikation und -verfolgung in Produktion und Logistik</b> Leitung: L. Brüll	Hall 10.1, Discussion Corner (Stand K3-N9)	11:30
<b>Matching function to application: a tool box of innovative encapsulation technologies for the chemical pharmaceutical industry</b> K. Köhler, D. Duff, M. Weiß, J. Uhlemann, Bayer Technology Services GmbH, Leverkusen/D	Illusion 3, CMF	15:30
<b>µ-PR – photoinduced processes with microstructured reactor technology</b> F. Schael, Ehrfeld Mikrotechnik BTS GmbH, Wendelsheim/D	Harmonie 3, CMF	17:00
<b>Capacity extension in the chemical and pharmaceutical industry by process analysis</b> H.-J. Leimkühler, Bayer Technology Services GmbH, Leverkusen/D	Illusion 2, CMF	17:00
WEDNESDAY	LOCATION	TIME
<b>Nickel based alloys – a chronological review</b> M. Renner, Bayer Technology Services GmbH, Leverkusen/D	Analog, Forum	11:00
<b>Central thermal oxidiser for waste gases of MDI and TDI production</b> I. Gorges, Bayer Technology and Engineering, Shanghai Co., Ltd./PRC; U. Westphal, Bayer Technology Services GmbH, Leverkusen/D	Consens, Hall 4.C	14:00
THURSDAY	LOCATION	TIME
<b>Keynote Lecture: Process analyser technology for advanced process control – applications and benefits</b> A. Plum, S. Tosch, Bayer Technology Services GmbH, Dormagen/D; G. Dünnebier, Bayer Technology Services GmbH, Leverkusen/D; A. Schocker, T. Kleinert, BASF SE, Ludwigshafen/D	Analog Forum	10:30
<b>Sustainable implementation of energy and climate efficiency</b> A. Jupke, M. Wolf, H.-J. Leimkühler, Bayer Technology Services GmbH, Leverkusen/D	Consens, Hall 4.C	11:30
<b>Namur Expertenrunden: MES – Gibt's was Neues für die Prozessindustrie?</b> Leitung: M. Zeller	Hall 10.1, Discussion Corner (Stand K3-N9)	11:30
<b>Operational excellence through risk based asset integrity management</b> M. Pfaffelhuber, J. Kämpfer, Bayer Technology Services GmbH, Leverkusen/D	Conclusio 2, CMF	14:00
FRIDAY	LOCATION	TIME
<b>Novel heat exchangers and reactors</b> O. Stange, P. Jahn, Ehrfeld Mikrotechnik BTS GmbH, Wendelsheim/D	Conclusio 2, CMF	10:30

